

ARTICLE

Supplementary Information

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High Yield Exfoliation of a Sub-Micron hexagonal Boron Nitride
 Using a Solvent Free Method

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Table S1 (002) peak position and (002) FWHM of A_I -Cl and A_I -F

	(002) Peak position	(002) FWHM
A – pristine <i>h</i> BN	26.707	0.378
A_I -LiCl	26.571	0.483
A_I -NaCl	26.667	0.461
A_I -KCl	26.686	0.487
A_I -LiF	26.457	0.469
A_{I-H} -NaF	26.628	0.485
A_{I-H} -KF	26.571	0.487

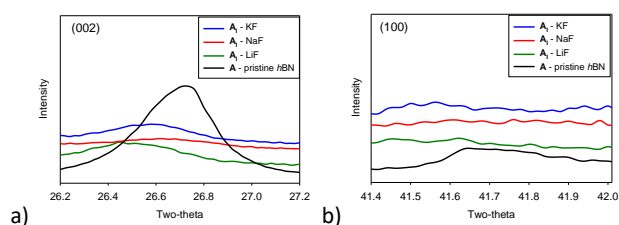


Figure S1 (a) and (b) XRD patterns of intercalated A_I -F on both (002) and (100) planes, respectively, using fluoride salts as activation agents. Note that (002) plane of pristine *h*BN was scaled down for observation and comparison to the exfoliated A_I -Cl.

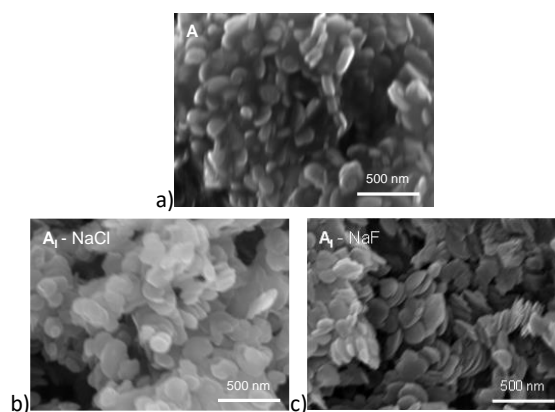


Figure S2 SEM images of (a) pristine *h*BN, (b) intercalated A_I using NaCl and (c) intercalated A_I using NaF as activation agents.

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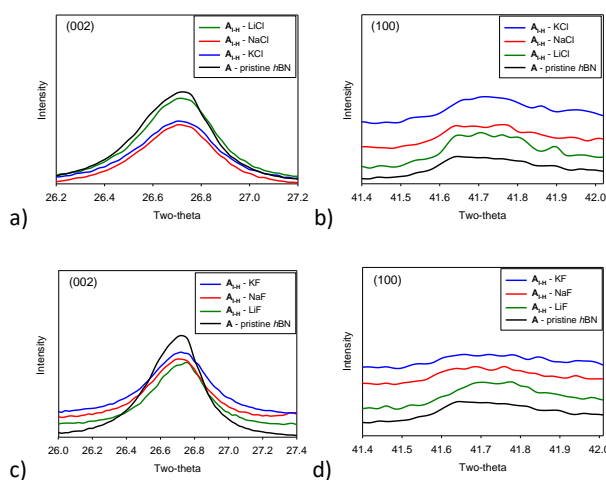
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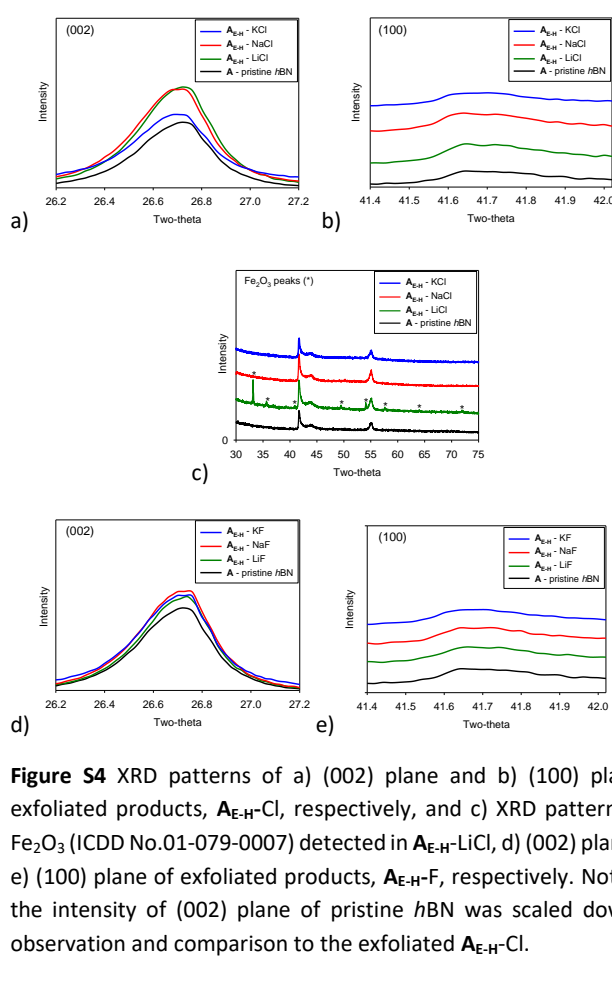
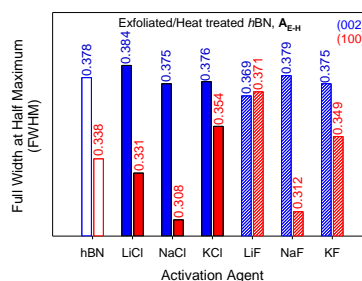
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Table S2 (002) peak position and (002) FWHM of A_{I-H-Cl} and A_{I-H-F}

	(002) Peak position	(002) FWHM
A – pristine <i>h</i> BN	26.707	0.378
$A_{I-H-LiCl}$	26.707	0.389
$A_{I-H-NaCl}$	26.707	0.335
$A_{I-H-KCl}$	26.707	0.357
$A_{I-H-LiF}$	26.745	0.362
$A_{I-H-NaF}$	26.726	0.389
A_{I-H-KF}	26.707	0.386

**Figure S3** XRD patterns of a) (002) plane and b) (100) plane of exfoliated products, A_{I-H-Cl} , c) (002) plane and d) (100) plane of exfoliated products, A_{I-H-F} , respectively. Note that the intensity of (002) plane of pristine *h*BN was scaled down for observation and comparison to the exfoliated A_{E-H-Cl} .**Table S3** (002) peak position of A_{E-H-Cl} and A_{E-H-F}

	(002) Peak position
A – pristine <i>h</i> BN	26.707
A_E-LiCl	26.724
A_E-NaCl	26.707
A_E-KCl	26.688
A_E-LiF	26.745
A_E-NaF	26.707
A_E-KF	26.707

**Figure S4** XRD patterns of a) (002) plane and b) (100) plane of exfoliated products, A_{E-H-Cl} , respectively, and c) XRD pattern of α - Fe_2O_3 (ICDD No.01-079-0007) detected in $A_{E-H-LiCl}$, d) (002) plane and e) (100) plane of exfoliated products, A_{E-H-F} , respectively. Note that the intensity of (002) plane of pristine *h*BN was scaled down for observation and comparison to the exfoliated A_{E-H-Cl} .**Figure S5** Full Width at Half Maximum (FWHM) of (002) and (100) planes of exfoliated/heat treated, A_{E-H} .**Table S4** % yield of A_{E-H} with different activation agents

A_{E-H}	% Yield
$A_{E-H-LiCl}$	>100
$A_{E-H-NaCl}$	>100
$A_{E-H-KCl}$	>100
$A_{E-H-LiF}$	93.0
$A_{E-H-NaF}$	83.6
A_{E-H-KF}	91.0

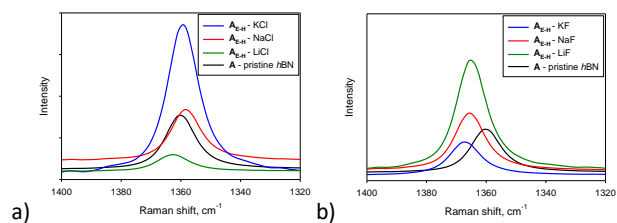


Figure S6 Raman spectroscopy of a) A_{E-H-Cl} and b) A_{E-H-F} , compared to **A**.

Table S5 Raman peak shift, peak height and FWHM of A_{E-H-Cl} and A_{E-H-F}

	Peak shift (cm^{-1})	Peak height	FWHM
A – pristine <i>h</i> BN	1360.2	2404	11.8
$A_{E-H-LiCl}$	1362.8	723	13.6
$A_{E-H-NaCl}$	1358.3	2242	11.9
$A_{E-H-KCl}$	1359.3	6541	12.1
$A_{E-H-LiF}$	1365.1	5986	13.5
$A_{E-H-NaF}$	1365.5	3071	11.0
A_{E-H-KF}	1367.2	1725	10.7